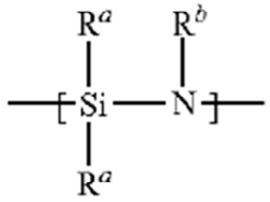
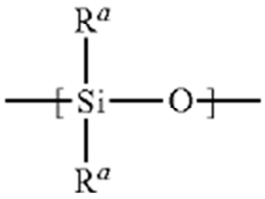
CLAIMS

1. A siloxazane compound having repeating units represented by the following general formulae (I) and (II)

(I)



(II)



wherein R^a and R^b each independently represent a hydrogen atom, an alkyl group, an alkenyl group, a cycloalkyl group, or an aryl group, provided that at least one of the two R^a bonded to one Si atom is a hydrogen atom,

in the siloxazane compound, the ratio of the number of O atoms to the total number of O atoms and N atoms is 5% or more and 25% or less, and

in the spectrum of the siloxazane compound obtained by ^{29}Si-NMR in accordance with the inverse gate decou-

pling method, the ratio of the area of the peak detected in −75 ppm to −90 ppm to the area of the peak detected in −25 ppm to −55 ppm is 4.0% or less.

2. The compound according to claim **1**, wherein the mass average molecular weight of the siloxazane compound is 1,500 or more and 52,000 or less.

3. The compound according to claim **2**, wherein R^a and R^b are hydrogen atoms.

4. A method for producing the compound according to claim **3**, which comprises reacting a perhydropolysilazane with water in the presence of an amine.

5. The method for producing the compound according to claim **4**, wherein the amine is pyridine.

6. A composition comprising the compound according to claim **3** and a solvent.

7. The composition according to claim **6**, wherein the solvent is selected from the group consisting of (a) aromatic compounds, (b) saturated hydrocarbon compounds, (c) unsaturated hydrocarbons, (d) ethers, (e) esters, and (f) ketones.

8. A method for producing the compound according to claim **1**, which comprises reacting a perhydropolysilazane with water in the presence of an amine.

9. The method for producing the compound according to claim **8**, wherein the amine is pyridine.

10. A composition comprising the compound according to claim **1** and a solvent.

11. The composition according to claim **10**, wherein the solvent is selected from the group consisting of (a) aromatic compounds, (b) saturated hydrocarbon compounds, (c) unsaturated hydrocarbons, (d) ethers, (e) esters, and (**0** ketones.

12. A method for producing a siliceous film, which comprises coating the composition according to claim **11** on a substrate and heating it.

13. The method for producing a siliceous film according to claim **12**, wherein the heating is performed in a steam atmosphere.

14. A method for manufacturing an electronic device, which comprises coating the composition according to claim **11** on a substrate and heating it.

15. A method for producing a siliceous film, which comprises coating the composition according to claim **10** on a substrate and heating it.

16. The method for producing a siliceous film according to claim **15**, wherein the heating is performed in a steam atmosphere.

17. A method for manufacturing an electronic device, which comprises coating the composition according to claim **10** on a substrate and heating it.